

**Amendments to the Claims:**

This listing of claims will replace the listing of claims as pending in the present application:

**Listing of Claims:**

Claim 1 (original): Ultrahigh purity copper having a residual resistance ratio of 38,000 or greater and a purity of 8N or higher (excluding gas components of O, C, N, H, S and P).

Claim 2 (original): The ultrahigh purity copper according to claim 1, wherein the respective elements of O, C, N, H, S and P as gas components are 1ppm or less.

Claim 3 (previously presented – Article 19): A manufacturing method of ultrahigh purity copper, wherein, upon subjecting copper to high purification with the electrolytic method, an anode and a cathode are partitioned with an anion exchange membrane, an anolyte is intermittently or continuously extracted, active carbon is poured in and agitated so as to absorb the impurities, the impurities are removed together with the active carbon by filtration, and the obtained high purity copper electrolytic solution is intermittently or continuously introduced into the cathode side and electrolyzed.

Claim 4 (canceled).